Simulation of Hyper-NA Immersion Lithography

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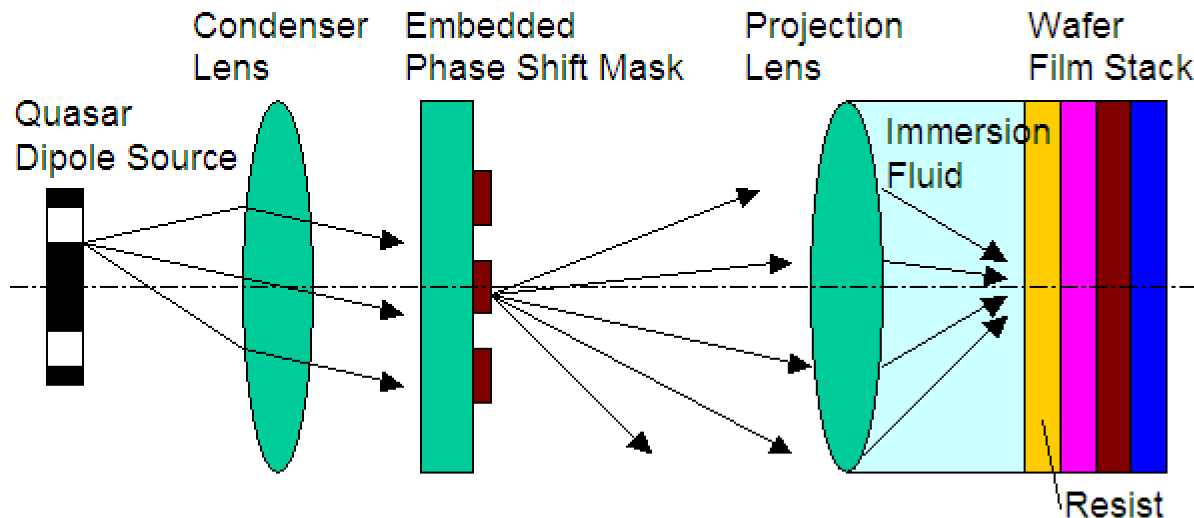
Simulation Setup

This example shows the use of the FDTD solver (for 3D thick mask simulation), the lens simulation engine and the film stack simulation engine. By cascading these simulation engines together via TCL scripts, the user is able to rigorously simulate a hyper-NA immersion lithography process under partially coherent oblique illumination.



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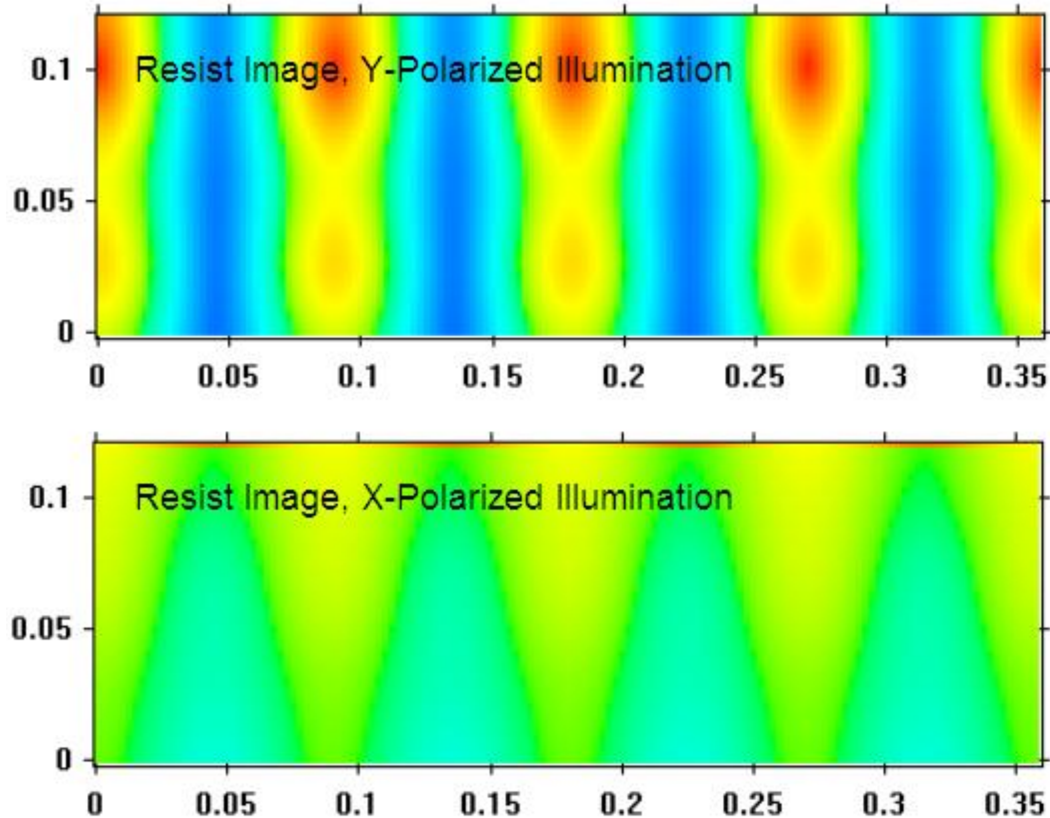
E-Field Intensity in Wafer Stack



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